






**POLYCYCLIC RESIST COMPOSITIONS WITH INCREASED ETCH RESISTANCE****Publication number:** JP2002504573 (T)**Publication date:** 2002-02-12**Inventor(s):****Applicant(s):****Classification:**

**- international:** C08F4/80; C08F32/08; C08F232/08; C08G61/06; C08G61/08; G03F7/004; G03F7/038; G03F7/039; C08F4/00; C08F32/00; C08F232/00; C08G61/00; G03F7/004; G03F7/038; G03F7/039; (IPC1-7): C08F32/08; C08F4/80; C08F232/08; C08G61/06; G03F7/004; G03F7/039

**- European:** C08G61/08; G03F7/004D; G03F7/038C; G03F7/039

**Application number:** JP20000532454T 19990219**Priority number(s):** US19980075557P 19980223; WO1999US03632 19990219**Also published as:**

 WO9942502 (A1)  
 TW250384 (B)  
 ID26627 (A)  
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 EP1058699 (A1)

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

Abstract not available for JP 2002504573 (T)

Abstract of corresponding document: **WO 9942502 (A1)**



Polycyclic polymers containing pendant aromatic moieties are disclosed. The polymers exhibit light transparency properties to deep UV wave lengths making them useful for high resolution photolithographic applications. These polymers are particularly useful in chemically amplified positive and negative tone resists.

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**POLYCYCLIC RESIST COMPOSITIONS WITH INCREASED ETCH RESISTANCE****Publication number:** WO9942502 (A1)**Publication date:** 1999-08-26**Inventor(s):** JAYARAMAN SAIKUMAR; GOODALL BRIAN L; RHODES LARRY F; SHICK ROBERT A; VICARI RICHARD; ALLEN ROBERT D; OPITZ JULIANN; SOORIYAKUMARAN RATNAM; WALLOW THOMAS**Applicant(s):** GOODRICH CO B F [US]**Classification:****- international:** C08F4/80; C08F32/08; C08F232/08; C08G61/06; C08G61/08; G03F7/004; G03F7/038; G03F7/039; C08F4/00; C08F32/00; C08F232/00; C08G61/00; G03F7/004; G03F7/038; G03F7/039; (IPC1-7): C08F32/08; C08F232/08; C08G61/08; G03F7/004; G03F7/039**- European:** C08G61/08; G03F7/004D; G03F7/038C; G03F7/039**Application number:** WO1999US03632 19990219**Priority number(s):** US19980075557P 19980223**Also published as:** TW250384 (B)  
 JP2002504573 (T)  
 ID26627 (A)  
 HK1035199 (A1)  
 EP1058699 (A1)

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**Cited documents:** EP0789278 (A2)  
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 EP0695733 (A1)

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**Abstract of WO 9942502 (A1)**

Polycyclic polymers containing pendant aromatic moieties are disclosed. The polymers exhibit light transparency properties to deep UV wave lengths making them useful for high resolution photolithographic applications. These polymers are particularly useful in chemically amplified positive and negative tone resists.

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